



## Future Normal in Semiconductor

2025-02-13(목), 15:50-17:20

좌장: 추후업데이트 예정

J. Nano-Science & Technology분과

### [TK3-J] Emerging Nanomaterials & Applications

<p>TK3-J-1 15:50-16:05</p>	<p><b>Mitigating Substrate Effects of van der Waals Semiconductors Using Perfluoropolyether Self-assembled Monolayers</b></p> <p>Dae Young Park<sup>1</sup>, Hyeong Chan Suh<sup>1</sup>, Seungho Bang<sup>1</sup>, Ju Chan Lee<sup>2</sup>, Jaekak Yoo<sup>1</sup>, Hayoung Ko<sup>2</sup>, Soo Ho Choi<sup>2</sup>, Ki Kang Kim<sup>2</sup>, Seung Mi Lee<sup>3</sup>, Seong Chu Lim<sup>2</sup>, Tschang-Uh Nahm<sup>1</sup> and Mun Seok Jeong<sup>1</sup></p> <p><sup>1</sup>Department of Physics, Hanyang University, <sup>2</sup>Department of Energy Science, Sungkyunkwan University, <sup>3</sup>KRISS</p>
<p>TK3-J-2 16:05-16:20</p>	<p><b>Facile Repairing Process of Sulfur Vacancy on MoS<sub>2</sub> Surface with Fluorinated Benzenethiol</b></p> <p>Mingyu Kim<sup>1</sup>, Haksoon Jung<sup>1</sup>, Yongwoo Lee<sup>2</sup>, Taoyu Zou<sup>1</sup>, Jimin Kwon<sup>2</sup>, and Yong-Young Noh<sup>1</sup></p> <p><sup>1</sup>Department of Chemical Engineering, POSTECH, <sup>2</sup>Department of Electrical Engineering, UNIST</p>
<p>TK3-J-3 16:20-16:35</p>	<p><b>Exploring the Piezoresistive Pressure Sensing Range in MOCVD-Grown Hierarchical Three-Dimensional MoS<sub>2</sub></b></p> <p>Jeongin Song<sup>1,2</sup>, Se Min Hwang<sup>1,3</sup>, Min Sup Choi<sup>3</sup>, Sang Woo Kang<sup>1,4</sup>, Taesung Kim<sup>2</sup>, and Jihun Mun<sup>1</sup></p> <p><sup>1</sup>KRISS, <sup>2</sup>Sungkyunkwan University, <sup>3</sup>Chungnam National University, <sup>4</sup>UST</p>
<p>TK3-J-4 16:35-16:50</p>	<p><b>Influence of Grain Size on Amplified Spontaneous Emission in Metal Halide Perovskite</b></p> <p>Hyeree Kim<sup>1</sup>, Seung-Je Woo<sup>2</sup>, Kyung Yeon Jang<sup>1</sup>, and Tae-Woo Lee<sup>1,3</sup></p> <p><sup>1</sup>Department of Material Science and Engineering, Seoul National University, <sup>2</sup>Cavendish Laboratory, University of Cambridge, UK, <sup>3</sup>Research Institute of Advanced Materials, Institute of Engineering Research, Soft Foundary, Interdisciplinary Program in Bioen</p>
<p>TK3-J-5 16:50-17:05</p>	<p><b>Enhanced Gating Efficiency in Vertical Mixed Molecular Transistors with Deep Orbital Level</b></p> <p>Donguk Kim, Hyemin Lee, Minwoo Song, Jongwoo Nam, and Takhee Lee</p> <p>Department of Physics and Astronomy, Seoul National University</p>



# 제 32회 한국반도체학술대회

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## *Future Normal in Semiconductor*

TK3-J-6 17:05-17:20	<b>Development of CMOS-Integrated TiOx Memristor Array for In-Memory Computing</b> Yeon Seo An <sup>1</sup> , Gunuk Wang <sup>1,2</sup> , Dowon Kim <sup>3</sup> , and Byunggeun Lee <sup>3</sup> <sup>1</sup> KU-KIST Graduate School of Converging Science and Technology, Korea University, <sup>2</sup> Department of Integrative Energy Engineering, Korea University, <sup>3</sup> GIST
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